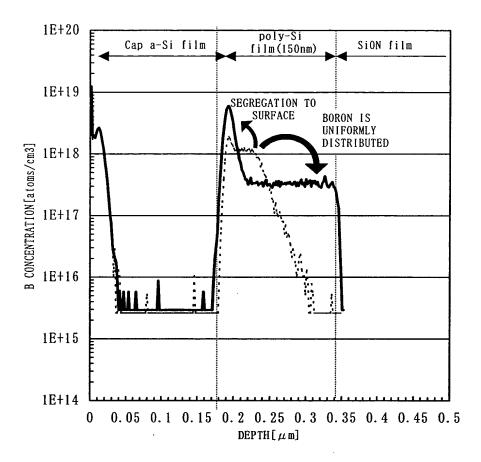
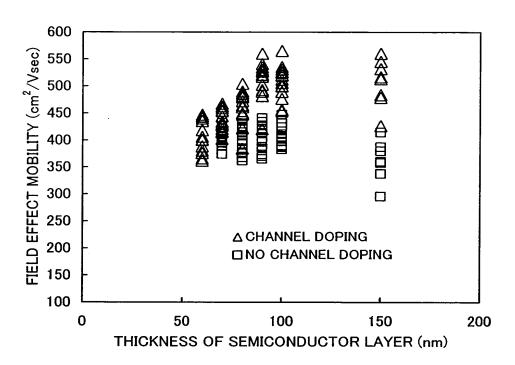
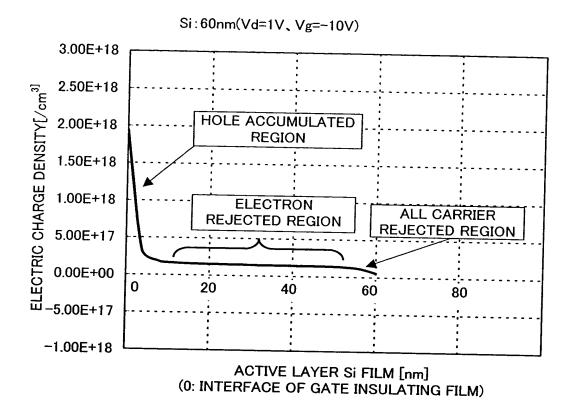
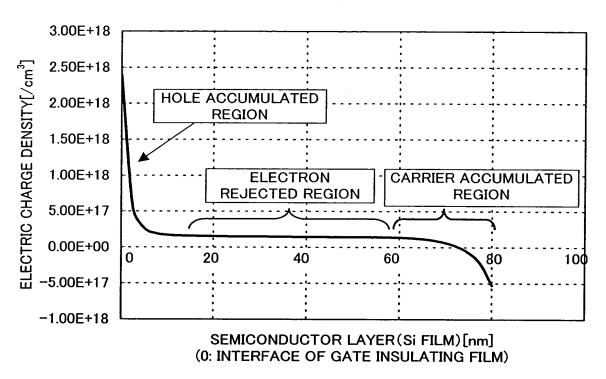
FIG.1

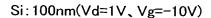


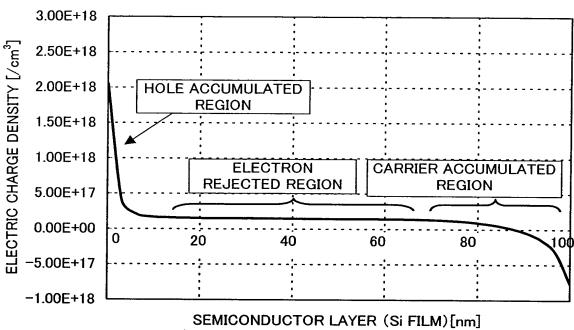




Si:80nm(Vd=1V, Vg=-10V)

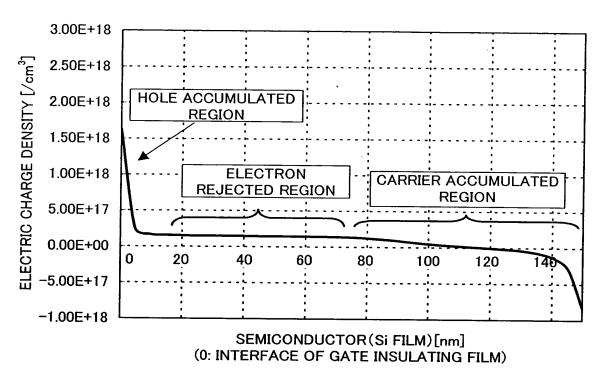


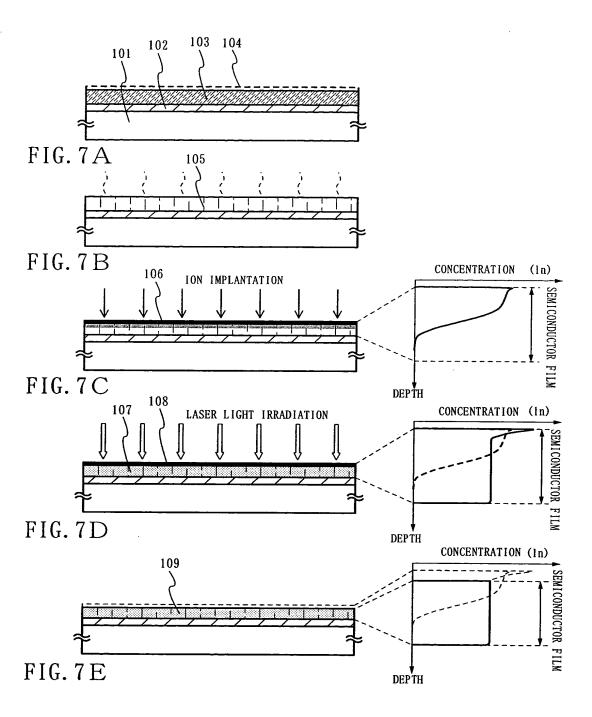


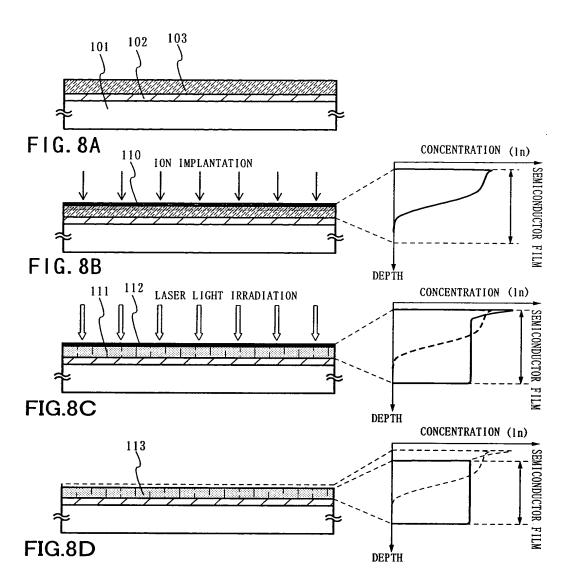


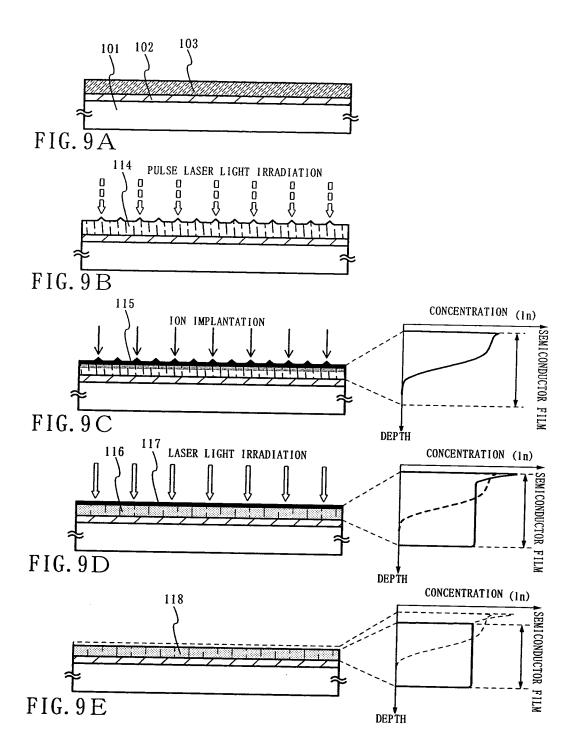
SEMICONDUCTOR LAYER (Si FILM)[nm]
(0: INTERFACE OF GATE INSULATING FILM)

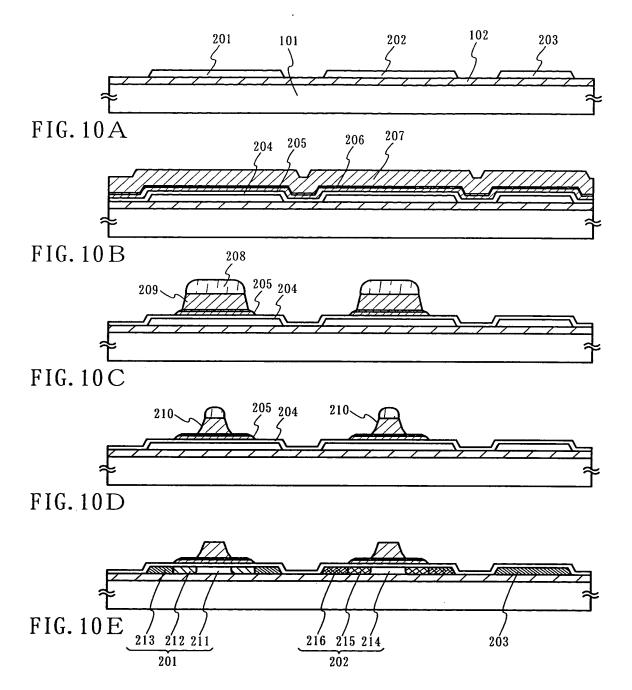
Si: 150nm(Vd=1V, Vg=-10V)

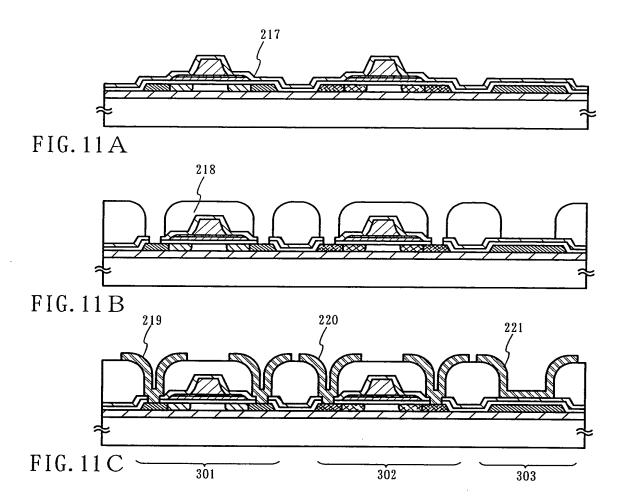


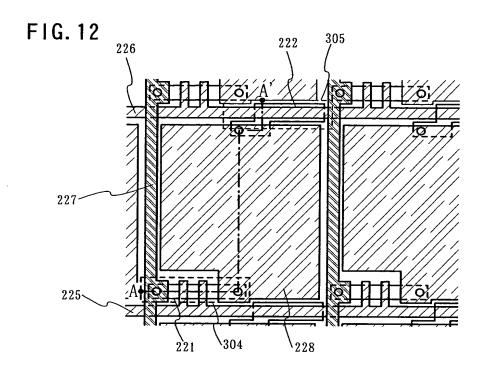


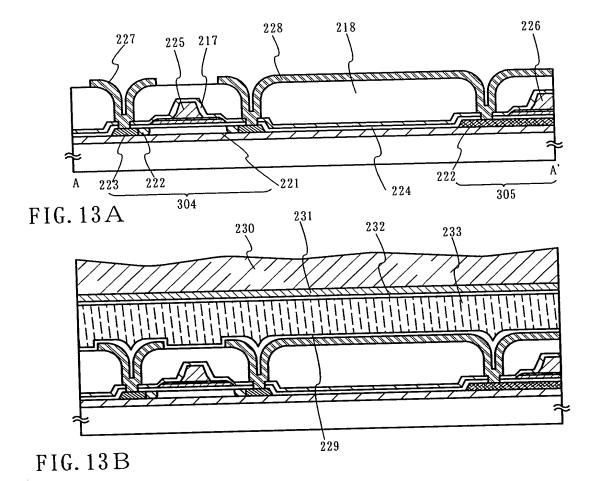


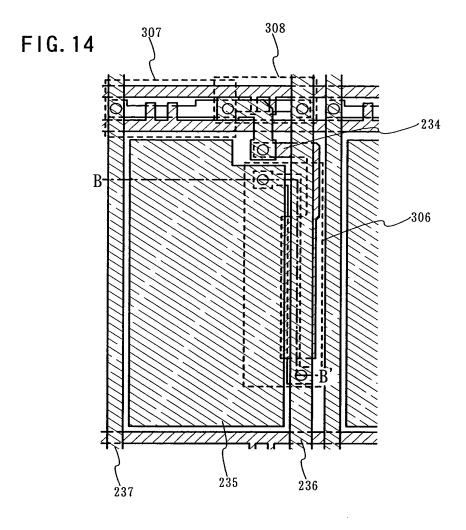


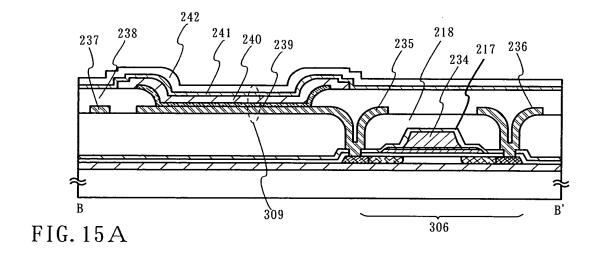












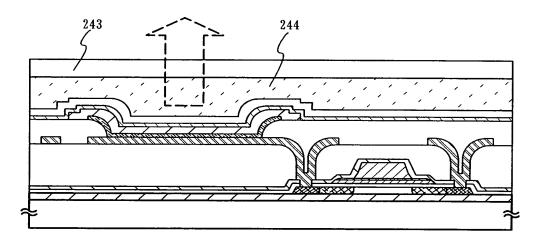


FIG. 15B

FIG. 16

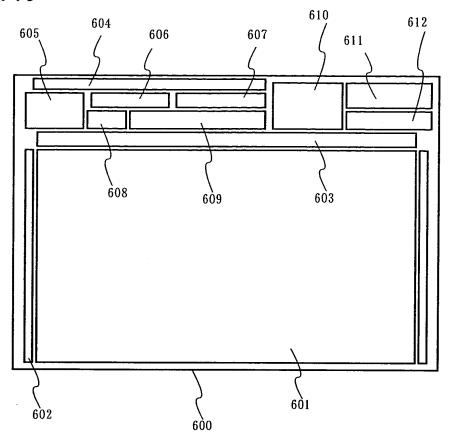


FIG. 17

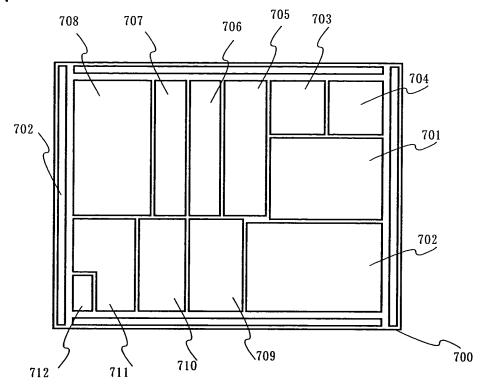


FIG. 18

